Corning® Advanced-Flow™ G1 Photo Reactor
Multipurpose Continuous Flow Photochemistry

Corning’s success with Advanced-Flow™ reactor technology has helped enable advances into the photochemical market. The Corning® Advanced-Flow™ G1 photo reactor utilizes the technology of the Corning® Advanced-Flow™ G1 reactor and the added benefit of ultraviolet light to enable photoreactions and a consistent distribution of UV light to chemicals ensuring:

- better performance
- higher yields
- higher productivity for photochemical reactions
- more homogeneous absorption of light through the depth of the reaction channel

The Corning® Advanced-Flow™ G1 photo reactor is intended for customers who require photochemistry and a specific source of light, while benefitting from the heat- and mass-transfer capabilities of an Advanced-Flow™ reactor.

Benefits

- **A Process Development Tool**
  - Up to 5 fluidic modules in series
  - Up to 10 LED arrays that can be controlled independently

- **A Pilot Scale Production Tool**
  - Flow range: 10 to 150 ml/min
  - Pressure range: up to 18 bar

Features

- Tunable UV LED irradiation source available in multiple wavelength arrays
  - 365 nm
  - 405 nm
  - Other wavelengths available on request

- Both sides of glass fluidic modules illuminated
  - Efficient light penetration

- Variable LED lighting intensity
  - Typically up to 80 mW / cm²

- Safe operation
  - Low temperature UV lighting technology

- Extended LED lifetime due to efficient liquid cooling

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